

In situ growth of Ni-MOF nanorods array on Ti₃C₂T_x nanosheets for electrodes

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1. Methods for calculation of specific capacitance

CV test

The gravimetric capacitances were calculated according to the following equations:

$$C_g = \frac{\int I dv}{2vm\Delta V}$$

Where C_g (F g⁻¹) is the gravimetric capacitance of the electrode, I (A) is the charge-discharge current, v (V/s) is the scan rate, m (g) is the mass of the working electrode. ΔV (V) is voltage window.

GCD test

The volumetric capacitances were calculated according to the following equations:

$$C_g = \frac{2i_m \int V dt}{V^2}$$

$$E = I/2 \cdot C_g V^2$$

$$P = E/t$$

Where C_g (F g⁻¹) is the gravimetric capacitance of the electrode, i_m (A) is the charge-discharge current density, Δt (s) is the discharge time, V (V) represents voltage drop on discharging, E (Wh·kg⁻¹) is the energy density of the electrode, P (W·kg⁻¹) is the power density of the electrode.

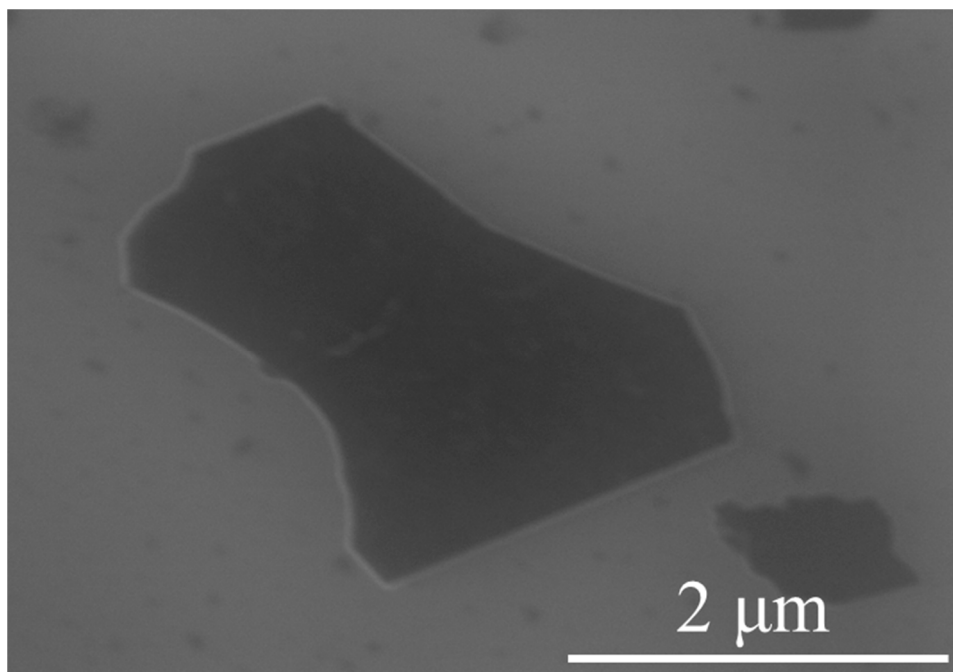


Figure S1. The SEM image of the $\text{Ti}_3\text{C}_2\text{T}_x$ nanosheets.

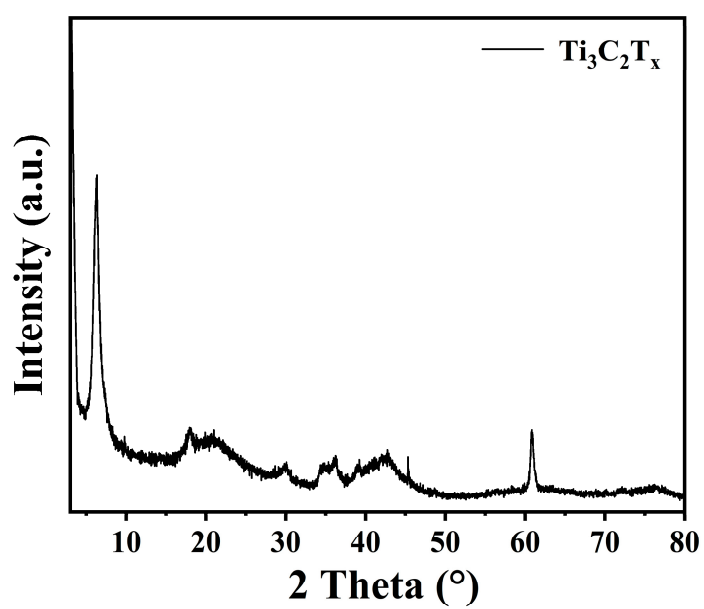


Figure S2. The XRD pattern of the $\text{Ti}_3\text{C}_2\text{T}_x$.

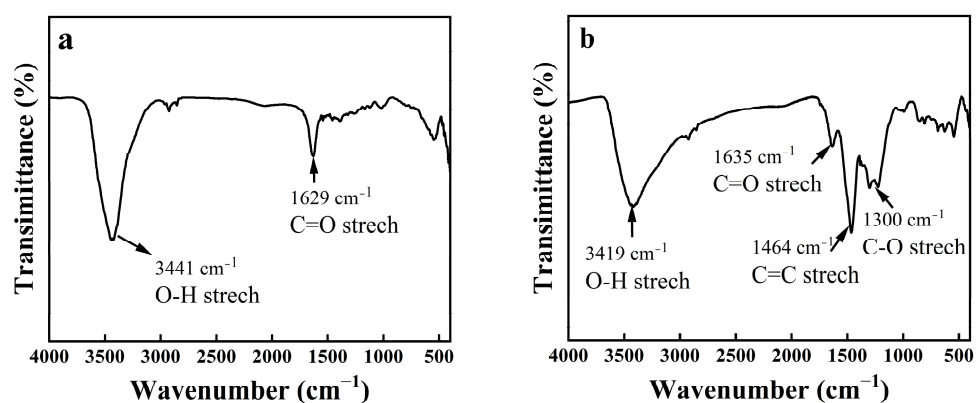


Figure S3. FT-IR pattern of (a) $\text{Ti}_3\text{C}_2\text{T}_x$ and (b) Ni-MOF, respectively.

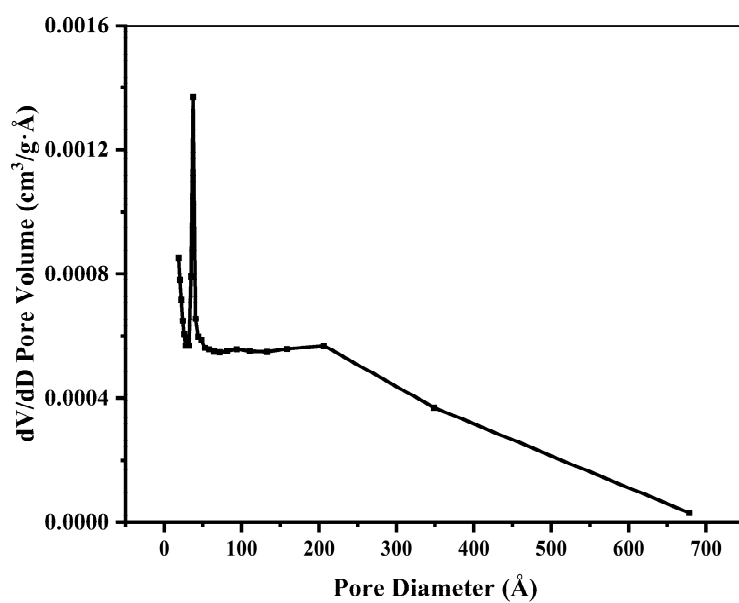


Figure S4. The pore size distribution of Ni-MOF/ $\text{Ti}_3\text{C}_2\text{T}_x$.

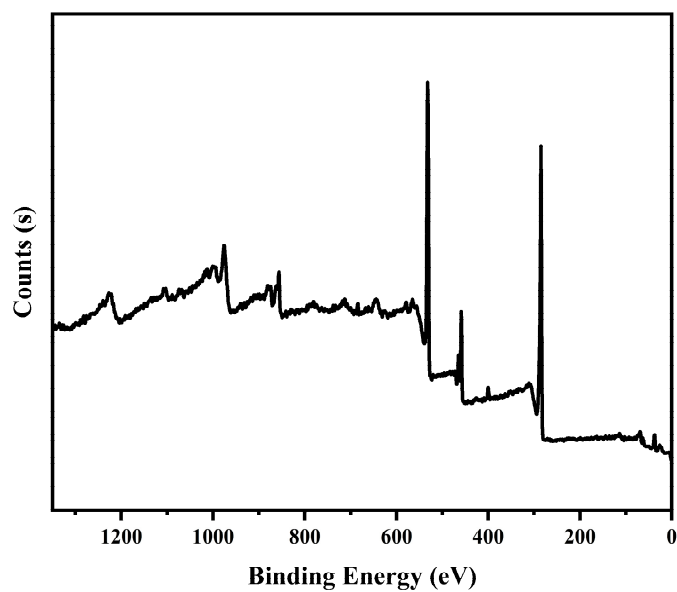


Figure S5. XPS spectra of Ni-MOF/Ti₃C₂T_x.

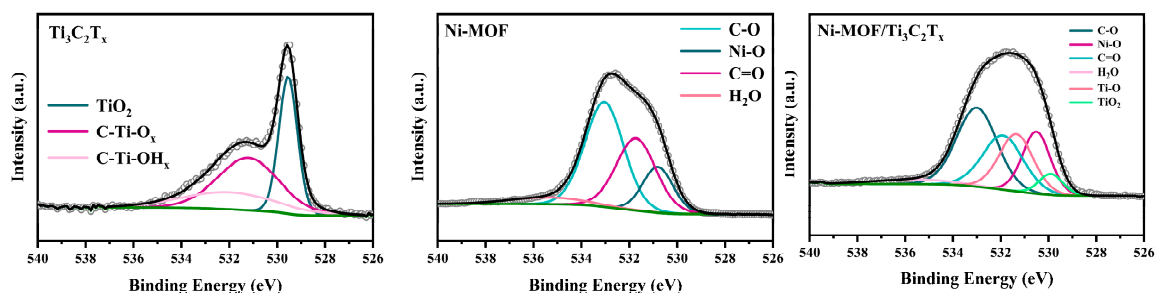


Figure S6. High-resolution O 1s spectra of Ti₃C₂T_x, Ni-MOF, Ni-MOF/Ti₃C₂T_x, respectively.

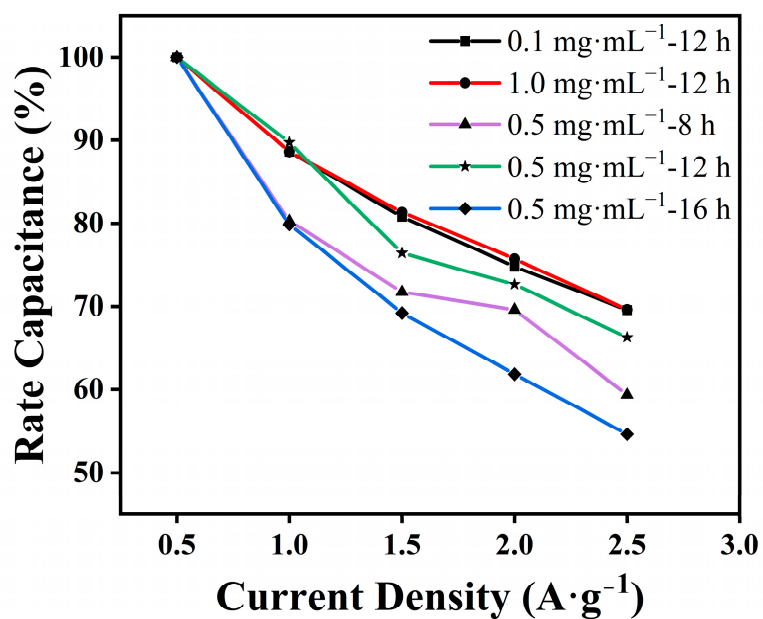


Figure S7. Comparison of rate capacitance of Ni-MOF/Ti₃C₂T_x, with different growth conditions.

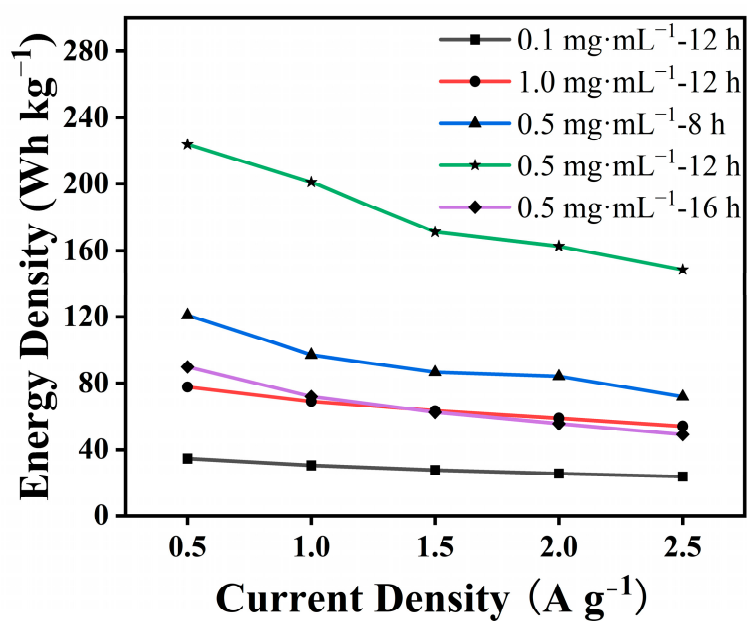


Figure S8. Comparison of energy density of Ni-MOF/Ti₃C₂T_x, with different growth conditions.

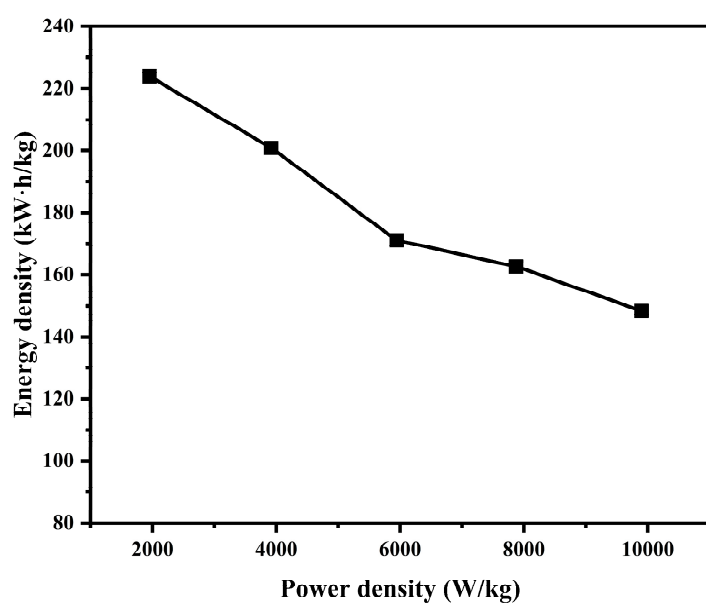


Figure S9. Energy density at different Power density of Ni-MOF/Ti₃C₂T_x.

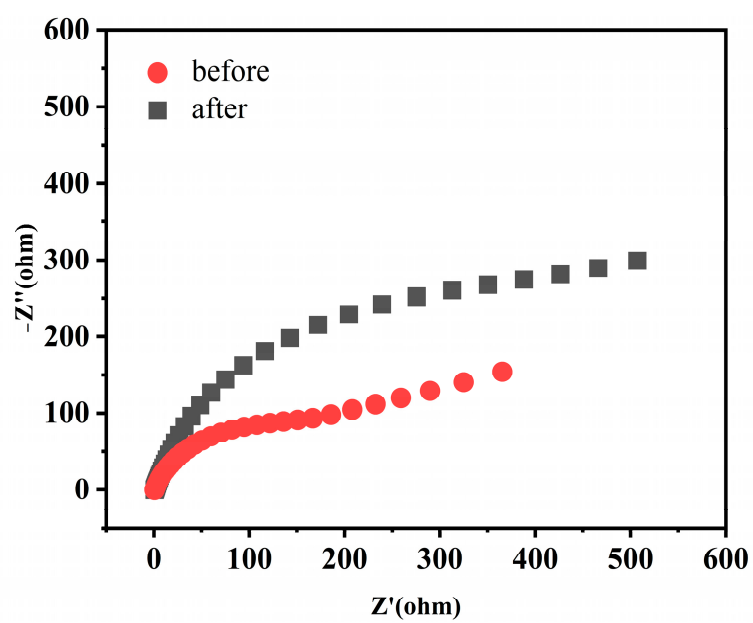


Figure S10. The EIS test of the Ni-MOF/Ti₃C₂T_x before and after stability test.

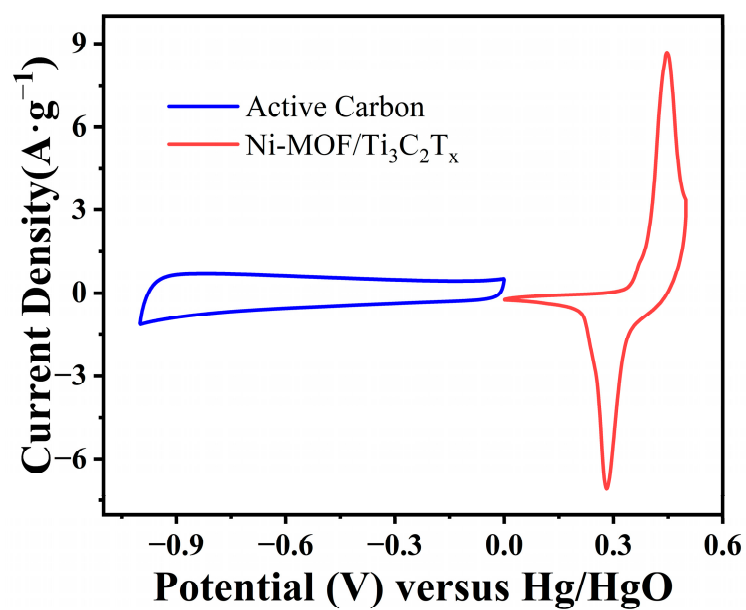


Figure S11. Energy density at different Power density of Ni-MOF/Ti₃C₂T_x.

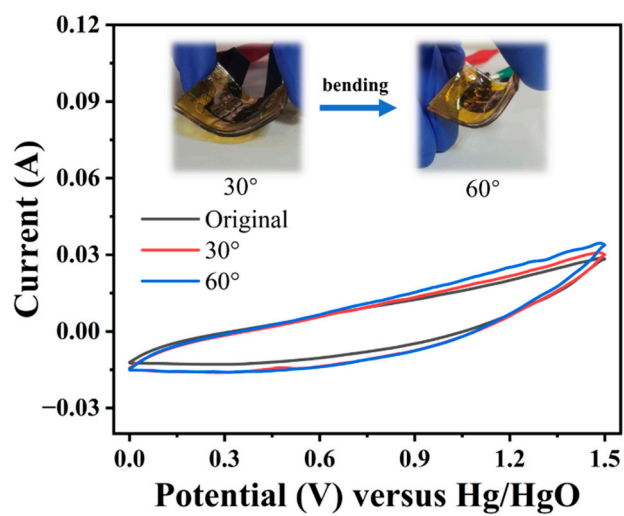


Figure S12. The CV test under original or bending states.